

Uttarakhand First Nanofabrication Facility

Why in News?

<u>IIT-Roorkee</u> has established a **cutting-edge** <u>nanofabrication</u> facility in Uttarakhand to advance <u>India's semiconductor manufacturing mission.</u>

Key Points

- International Collaboration:
 - IIT-Roorkee collaborated with **Taiwan's premier semiconductor institutions** to exchange expertise.
 - The Department of Science and Technology (DST) funded the project, which began in 2019.
- State-of-the-Art Infrastructure:
 - The facility features cutting-edge instruments, including:
 - 50 kV Electron Beam Lithography (EBL) system with 10nm resolution.
 - Inductively Coupled Plasma RIE (ICP-RIE), a key etching technology for semiconductor manufacturing.
 - Equipped with ultra-clean rooms featuring controlled environments:
 - Class 100 space (300 sq ft) and Class 1000 space (600 sq ft) for precision research.
- Research Applications:
 - The facility supports cutting-edge research in:
 - Quantum sensors
 - Spintronics
 - Memory devices
 - Thin-film devices
 - Photodetectors
 - Quantum optics
 - Photonic crystals

Department of Science and Technology

- The foundation of DST was laid on 3rd May 1971 along the model of National Science Foundation (NSF), USA.
- It provides funding and also makes policies and co-ordinates scientific work with other countries.
- It empowers scientists and scientific institutions and also works with a highly distributed system permeating stakeholders ranging from school college, PhD, Postdoc students, young scientists, startups and NGOs working in Science & Technology.
- DST's budget has increased over the years by 100%, which has allowed initiation of new programmes in a wide range of areas.



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